



Atty. Dkt. No. 047297-0137

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant: Hisatsugu KURITA *et al.*  
Title: SILICON WAFER CLEANING METHOD  
Appl. No.: 10/645,911  
Filing Date: 08/22/2003  
Examiner: Michail Kornakov  
Art Unit: 1746  
Confirmation No.: 8557

**AMENDMENT AND REPLY UNDER 37 CFR 1.116**

Mail Stop AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, Virginia 22313-1450

~~DO NOT  
ROUTE~~  
~~M/K~~  
~~11/21/06~~

Sir:

This communication is responsive to the Final Office Action dated August 3, 2006, concerning the above-referenced patent application.

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this document.

Remarks/Arguments begin on page 3 of this document.

Please amend the application as follows:

Entered  
N/RCE  
atd 12/4/06  
KJ  
12/8/06

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